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#4/A 6-22-00 R. Brade

PATENT Atty. Docket No. MIT-106

(5473/112)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT:

Michael Mermelstein

SERIAL NO.:

09/274,601

GROUP NO.:

2878

FILING DATE:

March 23, 1999

**EXAMINER** 

**David Spector** 

TITLE:

OPITCAL SYNTHETIC APERTURE ARRAY

Assistant Commissioner for Patents Washington, D.C. 20231

## **PRELIMINARY AMENDMENT**

Applicant hereby submits this preliminary amendment for entry in the above-referenced patent application.

In the Claims

06/22/2000 RGRADEN 00000001e 200531nd 09274101 1-4, 7, 9, 11-13, and 19-21:

01 FC:103

1. Anthterferometric microlithography [synthetic aperture] system for producing a spatially non-periodic pattern [in a region of overlap] comprising:

a source of <u>coherent</u> electromagnetic radiation producing a plurality of <u>coherent</u> electromagnetic beams;

a plurality of beam controllers, each of said beam controllers positioned to receive a respective one of said plurality of said coherent electromagnetic beams and direct said respective coherent electromagnetic beam into a [said] region of overlap defined by an intersection of all of said plurality coherent electromagnetic beams; and

Adjustent data: 02/23/2000 RERADEN 09274601 605/22/2000 RERADEN 00000001 20053: 09274601 501:07 201: